AMENDMENTS TO THE CLAIMS:

The listing of claims will replace all prior versions, and listings of claims in the application:

LISTING OF THE CLAIMS

1. (Currently Amended) [[An]] A process for the electrodeposition of a nickel or nickel-alloy coating on a substrate, the process comprising:

immersing the <u>a</u> metal substrate in a bath comprising nickel ions and an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^+R_1R_2R_3]_nX^n$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting [[or]] of hydrogen, methyl, ethyl, propyl, allyl, propyn, propanediol and combinations thereof; and X^n is an n-valent inorganic or organic anion; and

electrodepositing nickel onto the metal substrate.

- 2. (Currently Amended) The process according to claim 1 wherein Xⁿ is an n-valent anion-selected from the group <u>consisting</u> of chloride, bromide, fluoride, sulfate, acetate, and tetrafluoroborate.
- 3. (Currently Amended) The process according to claim 1 wherein the bath further comprises alloying metal alloys ions, and electrodepositing nickel onto the metal substrate comprises electrodepositing a nickel-alloy onto the metal substrate.
- 4. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions; and
 - b) an additive having the general formula:

$$\begin{array}{ll} \cdot & \text{H}_2\text{C=CHCH}_2\text{NR}_1\text{R}_2 & \text{or} \\ & [\text{H}_2\text{C=CHCH}_2\text{N}^+\text{R}_1\text{R}_2\text{R}_3]_n\text{X}^{n-1} \end{array}$$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting [[or]] of hydrogen, methyl, ethyl, propyl, allyl, propyn, propanediol and combinations thereof; and X^n is an n-valent inorganic or organic anion.

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- 5. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) at least one Class I brightener; and
 - c) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{\uparrow\uparrow}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting [[or]] of hydrogen, methyl, ethyl, propyl, allyl, propyn, propanediol and combinations thereof; and X^{r} is an n-valent inorganic or organic anion.

- 6. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) at least one Class II brightener; and
 - c) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^{\dagger}R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting [[or]] of hydrogen, methyl, ethyl, propyl, allyl, propyn, propanediol and combinations thereof; and X^{r_0} is an n-valent inorganic or organic anion.

- 7. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) at least one Class I brightener,
 - c) at least one Class II brightener; and
 - d) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^+R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting [[or]] of hydrogen, methyl, ethyl, propyl, allyl, propyn, propanediol and combinations thereof; and X^{n-1} is an n-1

valent inorganic or organic anion.

- 8. (Currently Amended) An aqueous acidic plating bath for the electrodeposition of a nickel or nickel alloy deposit on a substrate comprising:
 - a) nickel ions;
 - b) alloying metal ions;
 - c) at least one Class I brightener;
 - d) at least one Class II brightener; and
 - e) an additive having the general formula:

$$H_2C=CHCH_2NR_1R_2$$
 or $[H_2C=CHCH_2N^*R_1R_2R_3]_nX^{n-1}$

wherein R_1 , R_2 and R_3 are selected from the functional groups consisting [[or]] of hydrogen, methyl, ethyl, propyl, allyl, propyn, propanedlol and combinations thereof; and X^n is an n-valent inorganic or organic anion.

- 9. (Currently Amended) The bath according to claim 8 wherein the alloying metal ions are selected from the group consisting of iron, cobalt, tin, and zinc.
- 10. (Currently Amended) The bath according to claim 4 wherein Xⁿ is an n-valent anion-selected from the group consisting of chloride, bromide, fluoride, sulfate, acetate, and tetrafluoroborate.
- 11. (New) The process according to claim 3, wherein the alloying metal ions are selected from the group consisting of iron, cobalt, tin, and zinc.
- 12. (New) The aqueous acidic plating bath according to claim 4, wherein the additive comprises diallyalmine.
- 13. (New) The aqueous acidic plating bath according to claim 4, wherein the additive comprises triaallylamine.
- 14. (New) The aqueous acidic plating bath according to claim 4, wherein the additive comprises diallyldimethyl ammonium chloride.

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- 15. (New) The aqueous acidic plating bath according to claim 4, wherein the additive is present in an amount of from about 5 mg/l to about 160 mg/l.
- 16. (New) The aqueous acidic plating bath according to claim 4, wherein the additive is present in an amount of from about 5 mg/l to about 100 mg/l.
- 17. (New) The aqueous acidic plating bath according to claim 4, wherein the additive is present in an amount of from about 6 mg/l to about 80 mg/l.
- 18. (New) The process according to claim 1, wherein the additive comprises diallyalmine.
- 19. (New) The process according to claim 1, wherein the additive comprises triaallylamine.
- 20. (New) The process according to claim 1, wherein the additive comprises diallyldimethyl ammonium chloride.